

VAKSiS

R&D AND ENGINEERING

micks®



PRODUCT INFORMATION

Vaksis MiCKS platform is composed of prismatic vacuum chambers and involve the magnetron sputtering technique on glass panes or large wafers. It is mostly used for low-e coatings, anti-reflection coatings, electrochromic coatings, transparent conductive oxide coatings, nitride resistors, high conductivity coatings, etc.

TECHNICAL SPECIFICATIONS

Ultimate Vacuum Pressure	$\leq 5 \times 10^{-8}$ Torr
Substrate Size	up to 30 x 30 cm
Substrate Heating	max. 400°C
Cooling.....	Where necessary
Deposition Mode	Upward/Downward
Number of Sources	Up to 10
Loading	Using Load Lock Chamber
Control	Fully Automatic

POWER SOURCES

-DC and/or RF Power Supply for Sputtering Magnetron Source

SOFTWARE

System operation by user-friendly software. It is not only the automation and control software but also coating management software which allows the user design his/her specific coating experiments, examine the process parameters used in the past, and use the recipes/coatings developed in the past without hustle.

Human and machine safeties are prime importance in the operations performed by the software. A graphical user interface will allow the user to see the status of the system during operation.